

AMENDMENTS TO THE SPECIFICATION

Beginning at the paragraph on page 1, line 5, please amend as follows:

The present application is a continuation-in-part of U.S. Patent Application No. 09/457,410 (now U.S. Patent No. 6,643,616), filed December 7, 1999, and issued November 4, 2003, the benefit of which is claimed under 35 U.S.C. § 120.

Beginning at the paragraph on page 12, line 8, please amend as follows:

In particular, system memory 704 and non-volatile mass storage 708 are employed to store a working copy and a permanent copy of the programming instructions implementing the above described teachings of the present invention. System memory 704 and non-volatile mass storage 706 may also be employed to store the IC designs. The permanent copy of the programming instructions to practice the present invention may be loaded into non-volatile mass storage 708 in the factory, or in the field, using distribution source/medium 714 and optionally, communication interfaces 712. Examples of distribution medium 714 include recordable medium such as tapes, CDROM, DVD, and so forth. In one embodiment, the programming instructions are part of a collection of programming instructions implementing an EDA tool [[600 of]], e.g., 600a, 600b, or 600c such as shown in FIGURE 6. The constitutions of elements 702-714 are well known, and accordingly will not be further described.

Beginning at the paragraph on page 15, line 4, please amend as follows:

FIGURE 11B shows values of light intensity that may be calculated at the sample points 1010, 1012, [[1016]] 1014. For bright field masks where a polygon is created on a wafer by an area of chrome that blocks light, the light intensity generally increases with distance away from the edge of the polygon. Next, the curvature of the light intensity at the control site is

determined by estimating the light intensity at the tangential sample points 1016, 1018. The tangential sample points can be aligned with any of the sample points 1010, 1012, or 1014 or anywhere in between. For example, the tangential sample points may be placed where the slope of the light intensity in the normal direction has a particular value or where the light intensity has a particular value, etc. To compute the light intensity curvature, the difference, Δ_1 , between the left tangential sample point 1016 and the center sample point 1012 is determined and the difference, Δ_2 , between the center sample point 1012 and the right tangential sample point 1018 is determined. The curvature is then defined as the difference $\Delta_1 - \Delta_2$.